TRANSFER DEVICE AND CIRCULATION METHOD

ABSTRACT

A transfer device for loading and unloading substrates to and from a processing apparatus configured to process the substrates includes a main body including a transfer space in which a transfer robot configured to transfer the substrates is provided, and an upper space provided above the transfer space. The main body is configured to be capable of supplying a gas in the upper space to the transfer space. The main body further includes: a housing constituting the transfer space, the housing including a wall configured to form a front surface to which a load port configured to support a container for accommodating the substrates is connected, a rear surface to which a load lock provided in the processing apparatus is connected, and a pair of side surfaces connecting the front surface and the rear surface in a device depth direction and facing each other in a device width direction, and a plurality of column connected to the wall; an exhaust passage formed within the column and configured to discharge a gas in another space, which is separate from the transfer space and the upper space of the main body; a return passage formed within the column and configured to return at least a gas in the transfer space to the upper space; and an exhaust box provided inside the housing and configured to be supplied with the gas discharged from the exhaust passage and the gas in the transfer space. The return passage is configured to return the gas supplied into the exhaust box back to the upper space.

(Fig. 4)